



WEBINAR ANNOUNCEMENT

Fundamentals of Photomask Design

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Date: June 18, 2020

Time: 11:00 AM – 12:00 PM (EDT)

Abstract: The creation of a photomask set is the first step to producing any variety of semiconductor devices. Thinking through how each mask will be used and the processing steps around them will ensure a smoother process flow and greater device yield. A brief overview of the terminology, technology, techniques around photomask design & creation, and the tools needed to evaluate and fabricate a successful photomask set will be presented.

Bio: Mr. Ben Hollerbach is a Process-Equipment Engineer at Georgia Tech's Institute for Electronics and Nanotechnology. He started working for the IEN in 2005 while a student at Georgia Tech. After receiving his bachelor's degree in industrial design he began working full time for the IEN and in 2009 took over the management of the IEN's Mask Shop. Over the past 11 years Ben has managed the evolution of photomask production from the use of a 1970's era GCA Mann Pattern Generator & Stepper through first generation Laser Writers to today's modern Heidelberg MLA150 Maskless Aligners.

Who should attend: Faculty, scientists, engineers, researchers, and technical staff from university, company, or government labs who are interested in learning about, micro-fabrication, in particular, photomask design, as part of their research efforts.

Join the Online Event June 18th at this link: <https://bluejeans.com/167443096>